

### **Other Miscellaneous papers with Hydrogen Silsesquioxane (HSQ)**

- 1) S. Gorelick, F. Zhang, J.A. van Kan, H.J. Whitlow, F. Watt, “Adhesion of proton beam written high aspect ratio hydrogen silsesquioxane (HSQ) nanostructures on different metallic substrates”, Nuclear Instruments and Methods in Physics Research B 267 (2009) 3314–3318.
- 2) M. Peuker, M.H. Lim, Henry I. Smith, R. Morton, A.K. van Langen-Suurling, J. Romijn, E.W.J.M. van der Drift, F.C.M.J.M. van Delft, “Hydrogen Silsesquioxane, a high-resolution negative tone e-beam resist, investigated for its applicability in photon-based lithographies”, Microelectronic Engineering 61–62 (2002) 803–809
- 3) Philip A. Shields, Duncan W.E. Allsopp, “Nanoimprint lithography resist profile inversion for lift-off applications”, Microelectronic Engineering 88 (2011) 3011–3014.
- 4) Yuji Kang; Okada, M.; Omoto, S.; Haruyama, Y.; Kanda, K.; Matsui, S. “Room temperature nanoimprinting using spin-coated hydrogen silsesquioxane with high boiling point solvent”, Journal of Vacuum Science & Technology B (Microelectronics and Nanometer Structures), v 29, n 6, p 06FC03 (3 pp.), Nov. 2011
- 5) Ki-Yeon Yang, Sang-Chul Oh, Hyungwon Park, Heon Lee, “Novel fabrication technique for nanoscale hydrogen silsesquioxane structures using a direct printing technique”, J. Vac. Sci. Technol. B 29(5), Sep/Oct 2011